L Number	Hits	Search Text	DB	Time stamp
16	132	ZAMPINI-A ZAMPINI-ANTHONY	USPAT;	2004/07/07 11:08
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
17	72894	acetal ketal	USPAT;	2004/07/07 11:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
18	18	(ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal)	USPAT;	2004/07/07 11:09
			US-PGPUB;	
	-		EPO; JPO;	
10			DERWENT	
19	8	((ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal)) and ((acid	USPAT;	2004/07/07 12:36
		photoacid) adj labile)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
20	1322	(acetal ketal) and ((acid photoacid) adj labile)	USPAT;	2004/07/07 11:13
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
21	428	((acetal ketal) and ((acid photoacid) adj labile)) and (430/\$.ccls.)	USPAT;	2004/07/07 11:14
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
22	281	(fluorinated fluorine fluoro) and (((acetal ketal) and ((acid photoacid)	USPAT;	2004/07/07 11:26
		adj labile)) and (430/\$.ccls.))	US-PGPUB;	
			EPO; JPO;	
22	2.00	B (6.)	DERWENT	
23	3620	disulfide same oxygen	USPAT;	2004/07/07 11:27
			US-PGPUB;	
			EPO; JPO;	
2.4	240		DERWENT	·
24	312	(disulfide same oxygen) and (resist photoresist)	USPAT;	2004/07/07 11:46
			US-PGPUB;	
			EPO; JPO;	
ar	14	WP 101	DERWENT	
25	14	((disulfide same oxygen) and (resist photoresist)) and ((acid photoacid)	USPAT;	2004/07/07 11:45
		adj labile)	US-PGPUB;	
			EPO; JPO;	
26	160	(disulfide edi espera edi edi	DERWENT	
20	160	(disulfide adj compound) same (oxygen)	USPAT;	2004/07/07 11:56
			US-PGPUB;	
			EPO; JPO;	
27	0	((disulfide adi compound) some (our see)) and ((asid all a line))	DERWENT	000.40=40=44.4
21		((disulfide adj compound) same (oxygen)) and ((acid photoacid) adj labile)	USPAT;	2004/07/07 11:45
		idone)	US-PGPUB;	
	l		EPO; JPO;	
28	53	((disulfide adj compound) same (oxygen)) and (resist photoresist)	DERWENT	0004/05/05 40 05
20	33	((disumde adj compound) same (oxygen)) and (resist photoresist)	USPAT;	2004/07/07 12:37
			US-PGPUB;	
			EPO; JPO;	
29	11	(disulfide adj compound) and (resist photoresist) and ((acid photoacid)	DERWENT	2004/07/07 12 25
	''	adj labile)	USPAT;	2004/07/07 12:36
		adj tabricj	US-PGPUB;	
			EPO; JPO;	
30	312	2-mercaptothiazole	DERWENT	2004/07/07 12 22
50	312	2-тегсариннадие	USPAT;	2004/07/07 12:36
			US-PGPUB;	:
			EPO; JPO;	
			DERWENT	

32 14 2-mercaptothiazole and (resist photoresist) US-PGPUB; EPO; IPO; DERWENT USPAT; US-PGPUB; EPO; IPO; DERWENT US-PGPUB; EPO;	7/07 12:36 7/07 12:37 7/07 12:40 7/07 12:41 7/07 12:41
32 14 2-mercaptothiazole and (resist photoresist) USPAT; USPGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US	7/07 12:40 7/07 12:41 7/07 12:41
32	7/07 12:40 7/07 12:41 7/07 12:41
32	7/07 12:40 7/07 12:41 7/07 12:41
33 14 (2-mercaptothiazole and (resist photoresist)) not (2-mercaptothiazole and ((acid photoacid) adj labile)) 34 6014 (photoacid acid) adj labile 35 1167 alicylic admantyl USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB;	7/07 12:40 7/07 12:41 7/07 12:41
33 14 (2-mercaptothiazole and (resist photoresist)) not (2-mercaptothiazole and (acid photoacid) adj labile)) USPAT; USPAT	7/07 12:41 7/07 12:41
33	7/07 12:41 7/07 12:41
33	7/07 12:41 7/07 12:41
and ((acid photoacid) adj labile)) 34 6014 (photoacid acid) adj labile (photoacid acid) adj labile 35 1167 alicylic admantyl 36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant US-PGPUB; EPO; JPO; DERWENT US-PGPUB;	7/07 12:41 7/07 12:41
34 6014 (photoacid acid) adj labile 35 1167 alicylic admantyl 2004/0; 36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant EPO; JPO; DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DE	7/07 12:41
34 6014 (photoacid acid) adj labile 35 1167 alicylic admantyl 2004/0; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO;	7/07 12:41
34 6014 (photoacid acid) adj labile 35 1167 alicylic admantyl 36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-P	7/07 12:41
35 1167 alicylic admantyl US-PGPUB; EPO; JPO; DERWENT USPAT; admantyl norbornyl norbornene adamantane USPAT; admantyl norbornyl norbornene adamantane) US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;	7/07 12:41
35 1167 alicylic admantyl EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/07	
35 1167 alicylic admantyl USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; adamantyl norbornyl norbornene adamantane) 36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant DERWENT USPAT; 2004/03	
35 1167 alicylic admantyl USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPA	
36 36775 alicylic adamantyl norbornyl norbornene adamantane 36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant 30 293861 surfactant	
36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; U	'/07 12:41
36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant DERWENT USPAT; 2004/03 USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO;	7/07 12:41
36 36775 alicylic adamantyl norbornyl norbornene adamantane 37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant USPAT; US-PGPUB; EPO; JPO; DERWENT US-P	7/07 12:41
37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic USPAT; USPAT; USPGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; DERWENT USPAT; USPAT; USPAT; DERWENT USPAT; DE	707 12:41
2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic uSPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT;	
37 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant DERWENT USPAT; 2004/07 USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/07	
37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic adamantyl norbornyl norbornene adamantane) 38 6029 (organic adj solvent) and (basic adj compound) 39 293861 surfactant 2004/07 USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/07	
adamantyl norbornyl norbornene adamantane) US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT;	//07 12.42
38 6029 (organic adj solvent) and (basic adj compound) EPO; JPO; DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/0; DERWENT USPAT; DERWENT	707 12:42
38 6029 (organic adj solvent) and (basic adj compound) DERWENT USPAT; 2004/0; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/0; USPAT; 2004/0; DERWENT USPAT; 2004/0; DERWENT USPAT; 2004/0; DERWENT USPAT; 2004/0; DERWENT USPAT; DERWENT US	
38 6029 (organic adj solvent) and (basic adj compound) USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/07	
US-PGPUB; EPO; JPO; DERWENT USPAT; 2004/07	//O7 12·42
EPO; JPO; DERWENT USPAT; 2004/0;	107 12.42
39	
39 293861 surfactant USPAT; 2004/07	
	'/07 12·42
US-PGPUB;	707 12.12
EPO; JPO;	
DERWENT	
1 40 And A 12 And	/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT	
41 1876 (thiol disulfide thiolsulfonate) adj derivative USPAT; 2004/07	/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT	
	/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT 1797737 resin DERWENT 2004/07	10-
051 AT, 2004/07	/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT 44 9 (resin (resist photoresist)) and ((thiol disulfide thiolsulfonate) adj USPAT; 2004/07	107 10 10
2004/07	/07 12:48
EPO; JPO; DERWENT	
(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist US-PGPUB;	/07 12.E1
	/07 12:51
	⁄07 12:51
photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO;	/07 12:51
photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.)	
photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.) 46 47 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist USPAT; 2004/07)	/07 12:51 /07 13:07
photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.)	

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47	4	saWATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	USPAT;	2004/07/07 12:57
		WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	
		WATANABE-SATOSHI-C-O-SPECIALTY	EPO; JPO;	
		WATANABE-SATOSHI-SHIN-ETSU-CHE	DERWENT	
48	1177			2004/07/07 12 05
70	1177		USPAT;	2004/07/07 13:05
		WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	
1		WATANABE-SATOSHI-C-O-SPECIALTY	EPO; JPO;	
		WATANABE-SATOSHI-SHIN-ETSU-CHE	DERWENT	
49	2	(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	USPAT;	2004/07/07 13:05
Ì		WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	
		WATANABE-SATOSHI-C-O-SPECIALTY	EPO; JPO;	
		WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide		
			DERWENT	
	_	thiolsulfonate) adj derivative)		
50	0	2002303986.URPN.	USPAT	2004/07/07 13:05
51	145158	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT;	2004/07/07 13:09
			US-PGPUB;	1
<u> </u>			EPO; JPO;	
52	8	(/\$10th; a \$10 \$10 d; a, \$1 d a \$10 d;	DERWENT	
34	•	(1) The state of t	USPAT;	2004/07/07 13:13
		(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	US-PGPUB;	
		WATANABE-SATOSHI-C-O-NIPPON-ST	EPO; JPO;	
1		WATANABE-SATOSHI-C-O-SPECIALTY	DERWENT	
		WATANABE-SATOSHI-SHIN-ETSU-CHE)		
53	6	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and	USPAT;	2004/07/07 13:21
		(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	,	2004/07/07 13.21
			US-PGPUB;	
		WATANABE-SATOSHI-C-O-NIPPON-ST	EPO; JPO;	
		WATANABE-SATOSHI-C-O-SPECIALTY	DERWENT	
·		WATANABE-SATOSHI-SHIN-ETSU-CHE)) not		
		((WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI		
ļ		WATANABE-SATOSHI-C-O-NIPPON-ST		
		WATANABE-SATOSHI-C-O-SPECIALTY		
		WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide		
]				
	100614	thiolsulfonate) adj derivative))		
-	182614	thiol disulfide thiolsulfonate mercapto\$	USPAT;	2004/07/06 19:03
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2424	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT;	2003/09/03 11:18
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	2003/03/03 11.10
			EPO; JPO;	
	400160		DERWENT	
-	409168	resist photoresist	USPAT;	2003/08/28 17:00
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	17620	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT;	2003/09/03 16:59
		, , , , , , , , , , , , , , , , , , ,	US-PGPUB;	2003/03/03 10.33
			EPO; JPO;	
	22.47-	de la	DERWENT	
-	22477	(basic adj compound) (nitrogen-containing adj compound)	USPAT;	2003/09/03 16:59
			US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	
-	266188	surfactant	USPAT;	2003/09/03 16:59
		·		2003/03/03 10.39
			US-PGPUB;	
			EPO; JPO;	
		R. L. a. Box Lates	DERWENT	
-	1095	dissolution adj inhibitor	USPAT;	2003/09/03 17:00
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	L			

thiol disulfide thiolsulfonate mercaptos) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (ped (post-exposure ad) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (ped (post-exposure ad) delay) (post ad) exposure ad) and (resist photoresist) and (diacid photoacid) near generat34 (photoacid) near generat34 (p					
((Idicid photoacid) near generat\$4 (photoactive near compound)) ((Idicid idisulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and ((Idicid photoacid) near generat\$4) (photoactive near compound)) and (Ifferit photoacid) near generat\$4) (photoactive near compound)) and (Ifferit photoacid) near generat\$4) (photoacid) (post adj cexposure adj delay)) ((Idioi disulfide thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj delay) (post adj exposure adj delay)) and (resist photoresist) and ((Idioi photoacid) near generat\$4) (photoacid) near generat\$4)	-	98	(thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj		2003/08/28 17:01
((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and ((facid photoacid) near generat\$4) (photoacitive near compoundi)) and (interpretation of the photoacid) near generat\$4) (photoacitive near compoundi)) and (interpretation of the photoacid) near generat\$4) (photoacitive near compoundi)) and (interpretation of the photoacid) near generat\$4) (photoacitive near compoundi)) and (interpretation of the photoacid) near generat\$4) (photoacitive near compoundi)) and (interpretation of interpretation) (interpretation) (interpretation of interpretation) (interpretation) (interpre			delay) (post adj exposure adj delay)) and (resist photoresist) and	US-PGPUB;	
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((acid photoacid) near generat\$4) (photoactive near compound)) and compound) and ((acid photoacid) near generat\$4) (photoacid) and (pest exposure adj delay) (post adj exposure adj delay) and (resist photoresist) and (ped (post-exposure adj delay) (post adj exposure adj delay) and (resist photoresist) and (ped (post-exposure adj delay) (post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) near compound)) and (surfactant (dissolution adj inhibitor) ((basic adj compound) (nitrogen-containing adj compound)) and ((acid photoacid) near generat\$4) (photoacid) near compound) and ((acid photoacid) near generat\$4) (photoacid) near compound) and ((acid photoacid) near generat\$4) (photoacid) near compound) and ((acid photoacid) near compound) (nitrogen-containing adj compound) (nitrogen-containi	-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj		2003/08/28 17:01
"11" 92 (thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure ad) delay/ (post adj exposure adj delay)) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoactive near compound))) and surfactant (disolution adj inhibitor) ((basic adj compound)) and ((acid photoacid) near generat\$4) (photoactive near compound)) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) and (resist photoresist) and ((acid photoacid) near generat\$4) (photoacid) post adj exposure adj delay) (post adj exposure adj d					
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delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and didavid post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and (((acid photoacid) near generat\$4) (photoacive near compound)) and ((((acid photoacid) near generat\$4) (photoacive near compound)) and (((((acid photoacid) near generat\$4) (photoacive near compound))) and (((((((((((((((((((((((((((((((((((
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- 6888 (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist) 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant 30 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoactive near compound)) and (((acid photoacid) near generat\$4) (((acid photoacid	-	$ $ $ $ $ $			2003/08/28 18:38
- 6888 (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist) - 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and (((acid photoacid) near generat\$4) ((acid photoactive near compound)) and (((acid photoacid) near generat\$4) ((acid photoactive near compound)) and (((acid photoacid) near generat\$4) ((acid photoactive near compound)) and (((acid photoacid) near generat\$4) ((acid photoactive near compound)) and (((acid photoacid) near generat\$4) ((acid photoactive near compound)) and ((acid photoacid) near generat\$4) ((acid photoactive near compound)) and ((acid photoacid) near generat\$4) ((acid photoactive near compound)) and ((acid photoacid) near generat\$4) ((acid			(post-exposure adj delay) (post adj exposure adj delay))		
- 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist) 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;					
photoresist) 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant 73 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and ((((acid photoacid) near generat\$4) (photoactive near compound)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and (((basic adj compound) (nitrogen-containing adj EPO; JPO;		6000	(\$10thial\$10 \$10dia\\$ida\$10 \$10di \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \		
- 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;	_	0000			2003/08/28 18:40
To the first photoresist is and (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; LS-PGPUB; compound)) and ((basic adj compound) (nitrogen-containing adj LS-PGPUB; compound)			photoresist)		
- 71 ((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;					
photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant 30 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;	_	71	((\$10thio \$10 \$10diculfida\$10 \$10thiolantforms \$10) 1		2002/00/22 :: 55
compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant - 30 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO; JPO;		'	photoresist)) and (((acid photoacid) pear generate 4) (photoacid)		2003/09/03 11:30
compound)) and surfactant (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj DERWENT USPAT; US-PGPUB; EPO; JPO;			compound)) and ((basic adj compound) (nitrogen containing adj		
- 30 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;			compound)) and surfactant		
photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;	-	30	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonata\$10) and (resist		2004/07/07 12:51
compound)) and ((basic adj compound) (nitrogen-containing adj EPO; JPO;			photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	,	4004/0//0/ 12:31
			compound)) and ((basic adj compound) (nitrogen-containing adj		
		<u> </u>	compound)) and surfactant) and (dissolution adj inhibitor)	DERWENT	

-	25	((((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	USPAT; US-PGPUB;	2004/06/29 13:38
		compound)) and ((basic adj compound) (nitrogen-containing adj	EPO; JPO;	
		compound)) and surfactant) and (dissolution adj inhibitor)) not	DERWENT	
		((((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure	BERWEIN	
		adj delay) (post adj exposure adj delay)) and (resist photoresist) and		
		(((acid photoacid) near generat\$4) (photoactive near compound))) and		
		(surfactant (dissolution adj inhibitor) ((basic adj compound)		
		(nitrogen-containing adj compound)))) not ((thiol disulfide		
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post		
		adj exposure adj delay))))		
-	2	(ped (post-exposure adj delay) (post adj exposure adj delay)) near	USPAT;	2003/09/03 11:28
		stabilizer	US-PGPUB;	
		·	EPO; JPO;	
			DERWENT	
-	0	(ped (post-exposure adj delay) (post adj exposure adj delay)) near	USPAT;	2003/09/03 11:24
		(additive)	US-PGPUB;	
			EPO; JPO;	
1_	2430	ped (post-exposure adj delay) (post adj exposure adj delay)	DERWENT	2002/00/02 44 42
_	4430	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT;	2003/09/03 11:19
,			US-PGPUB; EPO; JPO;	
			DERWENT	
_	2163	(thiol disulfide thiolsulfonate) near derivative	USPAT;	2003/09/03 18:43
		. deliration	US-PGPUB;	2003/03/03 10.43
			EPO; JPO;	
			DERWENT	
-	0	((ped (post-exposure adj delay) (post adj exposure adj delay)) same	USPAT;	2003/09/03 18:16
		((thiol disulfide thiolsulfonate) near derivative)) not ((ped	US-PGPUB;	10.10
		(post-exposure adj delay) (post adj exposure adj delay)) near	EPO; JPO;	
		stabilizer)	DERWENT	
-	1	(ped (post-exposure adj delay) (post adj exposure adj delay)) same	USPAT;	2003/09/03 11:19
		((thiol disulfide thiolsulfonate) near derivative)	US-PGPUB;	
			EPO; JPO;	
	24	(nod (nod)	DERWENT	
-	21	(ped (post-exposure adj delay) (post adj exposure adj delay)) and ((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2003/09/03 11:19
		(triioi disumde thioisuhonate) near derivative)	US-PGPUB;	
			EPO; JPO;	
_	0	2002303986.URPN.	DERWENT USPAT	2003/09/03 11:23
-	705		USPAT;	2003/09/03 11:23
		agont	US-PGPUB;	2003/03/03 11:24
			EPO; JPO;	
			DERWENT	
-	10	(ped (post-exposure adj delay) (post adj exposure adj delay)) near5	USPAT;	2003/09/03 11:24
		(agent)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	236	(ped (post-exposure adj delay) (post adj exposure adj delay)) near6	USPAT;	2003/09/03 11:29
		stabil\$6	US-PGPUB;	
			EPO; JPO;	
		((and (northern active add at 1) () is the second of the	DERWENT	
-	1	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6	USPAT;	2003/09/03 11:29
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)	US-PGPUB;	
			EPO; JPO;	
_	225	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6	DERWENT	2002/00/02 16 50
	445	stabil\$6) and (resist photoresist)	USPAT;	2003/09/03 16:59
		stability of and (resist photoresist)	US-PGPUB;	İ
			EPO; JPO; DERWENT	
-	126948	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT;	2003/09/03 11:39
		,	US-PGPUB;	2003/03/03 11.39
			EPO; JPO;	
			DERWENT	

-	11	(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 11:52
			DERWENT	
-	2	("6099880").PN.	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 11:52
_	0	20020136981.URPN.	DERWENT	2002/00/02 12 07
-	112931	THIOL DISULFIDE THIOLSULFONATE	USPAT USPAT; US-PGPUB;	2003/09/03 12:07 2003/09/03 14:06
			EPO; JPO; DERWENT	
-	7137	(THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE	USPAT; US-PGPUB;	2003/09/03 14:06
			EPO; JPO; DERWENT	
-	1564	((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6	USPAT; US-PGPUB;	2003/09/03 14:17
			EPO; JPO;	
-	121	(((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)	DERWENT USPAT; US-PGPUB;	2003/09/03 14:17
			EPO; JPO; DERWENT	
-	15	(US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	USPAT;	2003/09/03 14:26
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or	US-PGPUB; JPO	
		US-20020147259-\$).did. or (JP-2002303986-\$).did.		
-	120	((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	USPAT; US-PGPUB;	2003/09/03 14:26
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	EPO; JPO; DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or	DERWEINI	
-	120	US-20020147259-\$).did. or (JP-2002303986-\$).did.) ((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 17:01
		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	US-PGPUB; EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (([ped]		
		(post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))		
	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 14:27
~	266458	surfactant	DERWENT USPAT; US-PGPUB;	2003/09/03 14:27
			EPO; JPO; DERWENT	

•				
-	0	((((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 14:27
İ		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or	1	
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4)		
		(photoactive near compound)) AND surfactant		
]_	0	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 14:28
	Ŭ	SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	2003/09/03 14:26
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or	DEKWENT	
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4)		
	111	(photoactive near compound))		
-	111	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 14:42
		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	
:	l	((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or		
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		
	İ	stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj	Ì	
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
	ļ	stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10]	
		\$10thiolsulfonate\$10)))) AND surfactant		

-	0	(((((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:04
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
-	5	\$10thiolsulfonate\$10)))) AND surfactant) AND (430/\$.CCLS.) (("5589312") or ("5344694")).PN.	USPAT; US-PGPUB;	2003/09/03 15:05
-	2	wo-9306529-\$.did.	EPO; JPO; DERWENT USPAT;	2003/09/03 15:06
	7	((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.	US-PGPUB; EPO; JPO; DERWENT	0000/00/00 17 00
		(((3309312) 01 (3344094)).PNJ 01 W0-9306529-\$.dld.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:06
-	8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:43
-	31	((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 15:22
_	31	(((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
	31	((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030039916-\$ or US-20030039916-\$ or US-20010044070-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))))		

	30	(((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (IP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 ((post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))))) NOT (((ped (post-exposure adj delay) (post	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
		adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))		
-	246076	stabilizer	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 17:51
-	12420	stabilizer and (resist photoresist)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	22496	(basic adj compound) (nitrogen-containing adj compound)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	266458	surfactant	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	1096	dissolution adj inhibitor	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00
-	42	(stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00

-	41	((stabilizer and (resist photoresist)) and (((acid photoacid) near	USPAT;	2003/09/03 17:01
		generat\$4) (photoactive near compound)) and ((basic adj compound)	US-PGPUB;	
	1	(nitrogen-containing adj compound)) and surfactant and (dissolution	EPO; JPO;	
		adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj	DERWENT	
		exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay)		
		(post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate)	1	
		near derivative)) ((ped (post-exposure adj delay) (post adj exposure		
		adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj		
		exposure adj delay)) near6 stabil\$6) same ((thiol disulfide		
		thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post		
		adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and		
 		(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))		
-	41	(((stabilizer and (resist photoresist)) and (((acid photoacid) near	USPAT;	2003/09/03 17:02
		generat\$4) (photoactive near compound)) and ((basic adj compound)	US-PGPUB;	į
!		(nitrogen-containing adj compound)) and surfactant and (dissolution	EPO; JPO;	
		adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj	DERWENT	
, !		exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay)		
,		(post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate)		
		near derivative)) ((ped (post-exposure adj delay) (post adj exposure		
		adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj		
		exposure adj delay)) near6 stabil\$6) same ((thiol disulfide		
		thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post		
		adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and		
		(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) not		
		((((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917		
		430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near		
		derivative)) not (((("5589312") or ("5344694")).PN.) or		
		wo-9306529-\$.did.)) not ((((((THIOL DISULFIDE THIOLSULFONATE		
) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST		
		PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or		
		US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or		
	,	US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or		
		US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or		
		US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		,
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped	i	
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10))))) NOT (((ped (post-exposure adj delay) (post		
1		adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj		
[İ	delay) (post adj exposure adj delay)) same ((thiol disulfide		
		thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post		
		adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay))		
		delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol		
ŀ	ļ	disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj		
1		delay) (nost adi exposure adi delay)) peace et-Life() and (main		
		delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist		
		photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10		
_	orr)))) stabilizer and ((420/270.1.420/200.420/220.420/220.420/227	LICDIT	0000100100
-	855	stabilizer and ((430/270.1 430/296 430/326 430/330 430/327	USPAT;	2003/09/03 18:01
		430/913 430/917 430/921 430/942).ccls.)	US-PGPUB;	
			EPO; JPO;	
	_	A Life and the last state of	DERWENT	
-	1	(stabilizer same ((thiol disulfide thiolsulfonate) near derivative)) and	USPAT;	2003/09/03 17:53
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	US-PGPUB;	
		430/921 430/942).ccls.)	EPO; JPO;	
			DERWENT	

-		53	stabilizer same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB;	2003/09/03 17:54
				EPO; JPO;	
				DERWENT	
-		854	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327	USPAT;	2003/09/03 18:02
			430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol disulfide thiolsulfonate) near derivative))	US-PGPUB; EPO; JPO;	
			distince (noisunonate) near derivative))	DERWENT	
-		706	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327	USPAT	2003/09/03 18:02
			430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol		
			disulfide thiolsulfonate) near derivative))		
-		116	stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2003/09/03 18:50
				US-PGPUB;	
				EPO; JPO; DERWENT	
_		4	(stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)) and	USPAT;	2003/09/03 18:51
			(resist photoresist)	US-PGPUB;	2003/03/03 10.51
				EPO; JPO;	
				DERWENT	
-		8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	USPAT;	2003/09/03 18:43
			430/921 430/942).ccls.	US-PGPUB;	
				EPO; JPO; DERWENT	
-		2163	(thiol disulfide thiolsulfonate) near derivative	USPAT;	2003/09/03 18:50
				US-PGPUB;	
				EPO; JPO;	
		126948	\$10thial\$10.\$10diculfida\$10.\$10thialaulfanata\$10	DERWENT	2002/00/02 10 14
-		120940	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT; US-PGPUB;	2003/09/03 18:44
				EPO; JPO;	
				DERWENT	
-		127073	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 18:50
			\$10disulfide\$10 \$10thiolsulfonate\$10)	US-PGPUB;	
				EPO; JPO; DERWENT	
_		10164	stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2003/09/03 18:50
			(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))	US-PGPUB;	2003/03/03 10:30
				EPO; JPO;	
	•	701		DERWENT	
-		701	(stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist	USPAT;	2003/09/03 19:55
			photoresist)	US-PGPUB; EPO; JPO;	
			1	DERWENT	
-		34	((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2004/07/07 12:51
			(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist	US-PGPUB;	
			photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	EPO; JPO;	
_		6896	(((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	DERWENT USPAT;	2003/09/03 19:55
			\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)	US-PGPUB;	2003/03/03 19.33
	Ì		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
				DERWENT	
-		52 <i>7</i>	((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	USPAT;	2003/09/03 19:55
			((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	US-PGPUB; EPO; JPO;	
			430/921 430/942).ccls.)	DERWENT	
-		493	(((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:55
			\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
			((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	EPO; JPO;	
			thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10	DERWENT	
			\$10thiolsulfonate\$10)) and (resist photoresist)) and ((430/270.1		
	ļ		430/296 430/326 430/330 430/327 430/913 430/917 430/921		
L			430/942).ccls.))		

-	233	((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	USPAT; US-PGPUB;	2003/09/03 19:59
	İ	((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1		
		430/296 430/326 430/330 430/327 430/913 430/917 430/921		
		430/942).ccls.))) and (\$5acid near generat\$3)		
-	233	(((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:59
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921		
		430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same		
		(((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10		
	1	\$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist))		
		and ((430/270.1 430/296 430/326 430/330 430/327 430/913		
		430/917 430/921 430/942).ccls.))		
-	233	((((((((((((((((((((((((((((((((((((((USPAT;	2003/09/03 19:59
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921		
		430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same		
		(((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10		
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist))		
		and ((430/270.1 430/296 430/326 430/330 430/327 430/913		
		430/917 430/921 430/942).ccls.))) and ((430/270.1 430/296 430/326		
		430/330 430/327 430/913 430/917 430/921 430/942).ccls.)		
-	2	(("6406828") or ("6218076")).PN.	USPAT;	2004/06/29 13:23
			US-PGPUB;	
		////20010044070#\\	EPO; JPO	
-	2	(("20010044070") or ("6395446")).PN.	USPAT;	2004/06/29 13:39
			US-PGPUB; EPO; JPO	
-	37	((((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist	USPAT;	2004/06/29 14:01
	,	photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	US-PGPUB;	2004/00/23 14:01
		compound)) and ((basic adj compound) (nitrogen-containing adj	EPO; JPO;	
		compound)) and surfactant) and (dissolution adj inhibitor)) not	DERWENT	
		((((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure		
		adj delay) (post adj exposure adj delay)) and (resist photoresist) and		
		(((acid photoacid) near generat\$4) (photoactive near compound))) and	į	
		(surfactant (dissolution adj inhibitor) ((basic adj compound)		
		(nitrogen-containing adj compound)))) not ((thiol disulfide		
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post adj exposure adj delay))))		
_	3	(("6280897") or ("4304841") or ("6406828")).PN.	LICDAT.	2004/07/07 11:09
		(02000) / OI (1301011 / OI (0400020 //.FIN.	USPAT; US-PGPUB;	2004/07/07 11:08
			EPO; JPO	
_	17800	(thiol disulfide thiolsulfonate mercapto\$) adj (compound derivative)	USPAT;	2004/07/06 19:04
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	_30 ,,0,,00 ,3,0,
	-		EPO; JPO;	
			DERWENT	
-	450751	photoresist resist	USPAT;	2004/07/06 19:04
			US-PGPUB;	
			EPO; JPO;	
L	<u> </u>		DERWENT	

-	5152	(photoacid acid) adj generator	USPAT;	2004/07/06 19:04	7
]]	Aprilia dela, adj generator	US-PGPUB;	2004/07/00 19:04	
			EPO; JPO;		l
			DERWENT		
-	1098651	solvent	USPAT;	2004/07/06 19:04	
		Sorrein	US-PGPUB;	2004/07/00 19:04	
			EPO; JPO;		١
			DERWENT		
-	35	((thiol disulfide thiolsulfonate mercapto\$) adj (compound derivative))	USPAT;	2004/07/06 19:08	
		and (photoresist resist) and ((photoacid acid) adj generator) and	l '	2004/07/06 19:08	
		solvent	US-PGPUB;		
		Joivent	EPO; JPO;		
-	0	jp-5550806-\$.did.	DERWENT	2004/07/06 40 00	
)p-5550000-#.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		١
-	0	jp-55050806-\$.did.	DERWENT	2004/07/06 40 00	l
)p-55050000-#.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		
	0	jp-550050806-\$.did.	DERWENT		ĺ
_	0]p-550050606-\$.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		İ
		in EC7EC40 & Jul	DERWENT		
-	0	jp-5675643-\$.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		
		'- FCO7FC 40 A 11 1	DERWENT		
-		jp-56075643-\$.did.	USPAT;	2004/07/06 19:09	i
			US-PGPUB;		
			EPO; JPO;		
	l J	i i	DERWENT	i	